ULTRASONIC FILTRATION FOR CMP SLURRY

ABSTRACT

The present invention relates to semiconductor processing. In particular, it relates to a tunable ultrasonic filter and a method of using the same for more effective separation of large particles from slurry. In one embodiment a standing wave is produced in the filter and large particles are accumulated at the nodes of the standing waves while the slurry is flowed out of the filter.

Fig. 5